

Supporting Information

Engineering Dimensionality and Band-Edges with Lone-Pair Cations to Achieve Superior X-ray Detection in Metal-Free Perovskites

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Experimental:

Materials preparation: Ammonium tetrafluoroborate (NH_4BF_4 , 99%), hydrazine monohydrochloride ($\text{N}_2\text{H}_5\text{Cl}$, 98%), tetrafluoroboric acid (HBF_4 , 40%), and N-N'-diazabicyclo[2.2.2] octane (DABCO, 98%) were purchased from Adamas Reagent. All reagents and chemicals were used as received without further purification.

Synthesis of DABCO- $\text{NH}_4(\text{BF}_4)_3$ powders: DABCO (1.12 g, 10 mmol), NH_4BF_4 (1.05 g, 10 mmol), and HBF_4 (40%, 5 mL) were dissolved in 25 mL H_2O and stirred at room temperature for 24 h. The mixed solution was evaporated using a rotary evaporator at 60°C , then the white precipitate was collected, washed with methanol several times. Finally, the white product was dried for 24 hours at 50°C in a vacuum oven.

Synthesis of DABCO- $\text{N}_2\text{H}_5(\text{BF}_4)_3$ powders: The synthesis was performed following the same procedure as for DABCO- $\text{NH}_4(\text{BF}_4)_3$, with the only replacement of NH_4BF_4 with $\text{N}_2\text{H}_5\text{Cl}$ (0.68 g, 10 mmol). Additionally, the reaction was conducted in 10 mL H_2O and stirred for 12 h, with subsequent evaporation, washing, and drying steps remaining identical.

Synthesis of DABCO- $\text{NH}_4(\text{BF}_4)_3$ SCs: The DABCO- $\text{NH}_4(\text{BF}_4)_3$ single crystals were grown by dissolving the DABCO- $\text{NH}_4(\text{BF}_4)_3$ powders into deionized water to form a saturated solution. Then, the impurities in the mixture solution were removed by filtration, and the clear filtrate was transferred into a crystallizing dish and held at a constant temperature of 40°C in the oven for several days to afford single crystals.

Synthesis of DABCO- $\text{N}_2\text{H}_5(\text{BF}_4)_3$ SCs: The DABCO- $\text{N}_2\text{H}_5(\text{BF}_4)_3$ single crystals were grown by dissolving the DABCO- $\text{N}_2\text{H}_5(\text{BF}_4)_3$ powders into deionized water to form a saturated solution. Then, the impurities in the mixture solution were removed by filtration, and the clear filtrate was transferred into a crystallizing dish and held at a constant temperature of 35°C in the oven for several days to afford single crystals.

Single-Crystal Structure Determination: Single crystal of DABCO- $\text{NH}_4(\text{BF}_4)_3$ and DABCO- $\text{N}_2\text{H}_5(\text{BF}_4)_3$ were selected for single-crystal X-ray diffraction (SCXRD) measurements, with diffraction data collected on a Rigaku Mercury CCD diffractometer at room temperature. The diffractometer was equipped with graphite-monochromatized $\text{Cu K}\alpha$ radiation ($\lambda = 1.54184 \text{ \AA}$). Data reduction was implemented via the CrysAlisPro software package, and absorption corrections were applied using the multi-scan method. The crystal structure was solved by direct methods and refined through full-matrix least-squares fitting on F^2 with SHELXL within the OLEX2¹ program suite. Structural validation was performed using the PLATON² software. Crystallographic data and structure refinement details for DABCO- $\text{NH}_4(\text{BF}_4)_3$ and DABCO- $\text{N}_2\text{H}_5(\text{BF}_4)_3$ were summarized in Table S3, while atomic coordinates, equivalent isotropic displacement parameters, selected bond lengths and angles, as well as anisotropic displacement parameters are provided in Tables S4-S9.

Powder X-ray diffraction (PXRD): X-ray diffraction (XRD) patterns of the polycrystalline samples were collected on a Miniflex600 powder diffractometer with $\text{Cu K}\alpha$ radiation ($\lambda = 1.540598 \text{ \AA}$) at room

temperature, covering a 2θ range of $10-60^\circ$ with a scanning step size of 0.02° . The experimental and simulated powder XRD patterns of DABCO-NH₄(BF₄)₃ and DABCO-N₂H₅(BF₄)₃ were presented in Figures S2-S3.

Energy-dispersive X-ray Spectroscopy Analysis: Microprobe elemental analyses were performed by a field emission scanning electron microscope (FESEM, SU-8010) with energy dispersive X-ray spectroscope. The DABCO-NH₄(BF₄)₃ and DABCO-N₂H₅(BF₄)₃ crystals were washed by alcohol and mounted on an aluminum sample stage (Figures S6-S7).

Thermal analysis: Thermogravimetric Analysis (TGA) was performed by using a Netzsch STA449F3 simultaneous analyzer under flowing N₂ at a rate of $10^\circ\text{C}\cdot\text{min}^{-1}$. The DABCO-NH₄(BF₄)₃ and DABCO-N₂H₅(BF₄)₃ polycrystalline samples were placed in an Al₂O₃ crucible with another empty Al₂O₃ crucible used as the reference, and heated from 30°C to 550°C (Figures S8-S9).

First-principles calculations:

Band structure and partial density of states (PDOS) calculations for DABCO-NH₄(BF₄)₃ and DABCO-N₂H₅(BF₄)₃ were performed via the CASTEP³ code, a plane-wave pseudopotential total energy package based on density functional theory (DFT).⁴ The regularized Strongly Constrained and Approximately Correct (rSCAN) functional within the meta-generalized gradient approximation (m-GGA) was adopted to describe the exchange-correlation energy. A high plane-wave kinetic energy cutoff of 898.0 eV and a Monkhorst-Pack⁵ k-point mesh of $2 \times 2 \times 1$ were carefully selected for numerical integration over the Brillouin zone. Calculations of electron density, charge distribution and electrostatic interactions were conducted using the CP2K package,⁶ while the climbing image nudged elastic band (CI-NEB) method was employed to determine the potential barrier energy.⁷ Defect formation energy was calculated according to formula (1),⁸ and the independent gradient model based on Hirshfeld partition (IGHM)⁹ diagrams were plotted using the Multiwfn¹⁰ and VMD¹¹ software packages.

$$E = E_{defect} - E_0 - \sum_i n_i \mu_i + q(E_f - E_{VBM}) \quad (1)$$

The E_{defect} and E_0 represent the total energies of the same supercell with and without defects, respectively. The n_i represents the change in the number of atoms introduced as a defect. The μ_i represents chemical potential of element i . The E_f and E_{VBM} represent the Fermi level and the energy of the valence band top of a perfect crystal, respectively.

Device parameters:

$\mu\tau$ product calculation: In this work, a device structure of Ag/DABCO-NH₄(BF₄)₃ SC/Ag and Ag/DABCO-N₂H₅(BF₄)₃ SC/Ag were used for photoconductivity measurement. Then, the simplified Hecht equation (2) was utilized to extract the $\mu\tau$ product from photoconductivity curves, as follows:

$$I = \frac{I_0 \mu\tau V}{d^2} \left[1 - \exp\left(-\frac{d^2}{\mu\tau V}\right) \right] \quad (2)$$

where I_0 is the saturated photoinduced current, V is the bias voltage, and d is the device thickness.

X-ray detectors: X-ray detection measurements were conducted on a modified Super Nova setup, with X-rays emitted from a tungsten anode tube operating at a fixed accelerating voltage of 40 keV . All X-

ray response characterizations were performed in a dark environment shielded by a blackout curtain, and the photocurrent was recorded via a high-precision Keithley 6517B electrometer. All tests were carried out at room temperature.

Signal-to-noise ratio (SNR) calculation: The SNR is calculated according to the relation: $SNR = I_{\text{signal}}/I_{\text{noise}}$, where the signal current (I_{signal}) is the difference between the average photocurrent and the average dark current, and the noise current (I_{noise}) is obtained by calculating the standard deviation of the photocurrent.

Dark current drift (D) calculation: The D is calculated according to the relation $D=|J_{\text{finish}}-J_{\text{begin}}|/(t \times E)$, where t is duration, E is applied electric field, J_{finish} and J_{begin} represent current density at the end and beginning, respectively.

Gain factor calculation: The gain factor can be calculated as follows:

$$\text{Gain factor} = \frac{I_R}{I_P}$$

where I_R and I_P stand for induced photocurrent and theoretical photocurrent under X-ray illumination. I_R can be obtained in the experiment, while I_P should calculate as formula (3):

$$I_P = \varphi \beta e \quad (3)$$

The φ (photon absorption rate) is defined as: $\varphi = \frac{\varepsilon D m_s}{E_{ph}}$

where β (the number of excited carriers per X-ray photon) is defined as: $\beta = \frac{E_{ph}}{1.43 + 2E_g}$

Notably, e represents electric charge, ε is the photon absorption fraction of the sample, D represents the dose rate, m_s is the mass of the sample, and E_{ph} is X-ray energy, E_g represents the band gap.

Goldschmidt tolerance factor calculation:

$$t = \frac{R_A + R_X}{\sqrt{2}(R_B + R_X)} \quad (4)$$

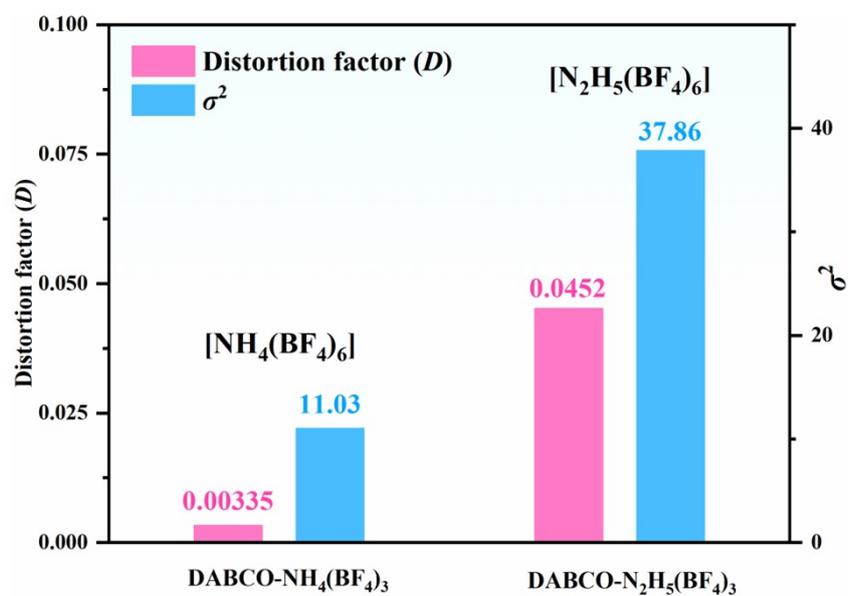


Figure S1. The comparison of distortion factors and bond angle variances of adjacent octahedra in DABCO- $\text{NH}_4(\text{BF}_4)_3$ and DABCO- $\text{N}_2\text{H}_5(\text{BF}_4)_3$.

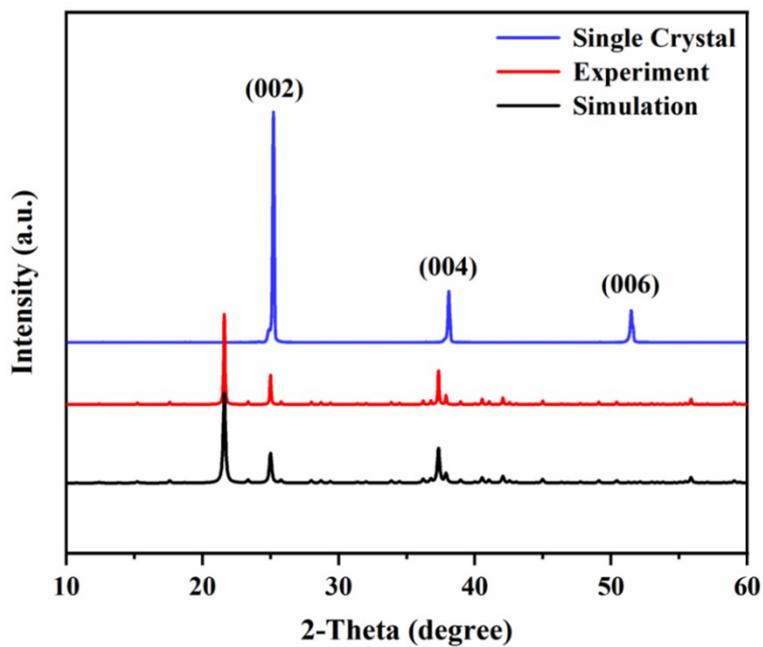


Figure S2. X-ray diffraction patterns of DABCO- $\text{NH}_4(\text{BF}_4)_3$ single crystal and its simulated and experimental powder.

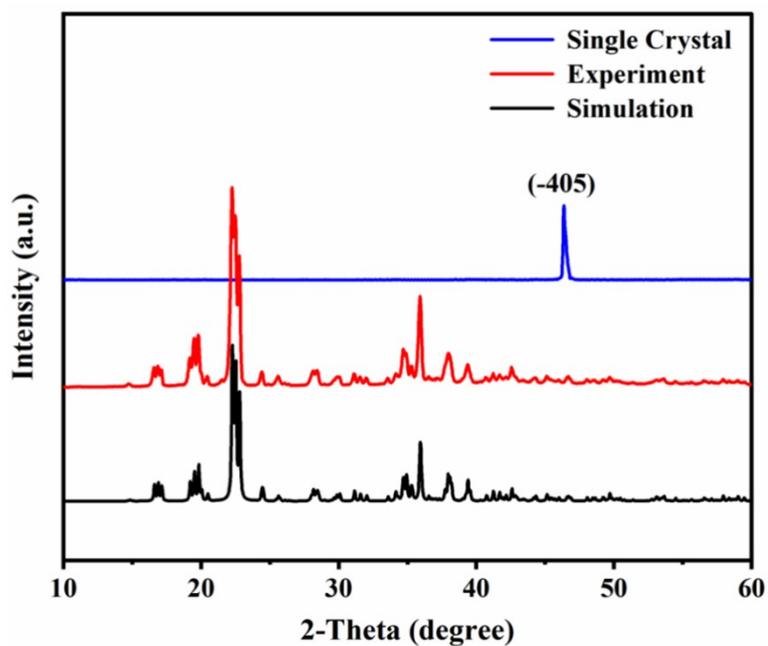


Figure S3. X-ray diffraction patterns of DABCO- $\text{N}_2\text{H}_5(\text{BF}_4)_3$ single crystal and its simulated and experimental powder.

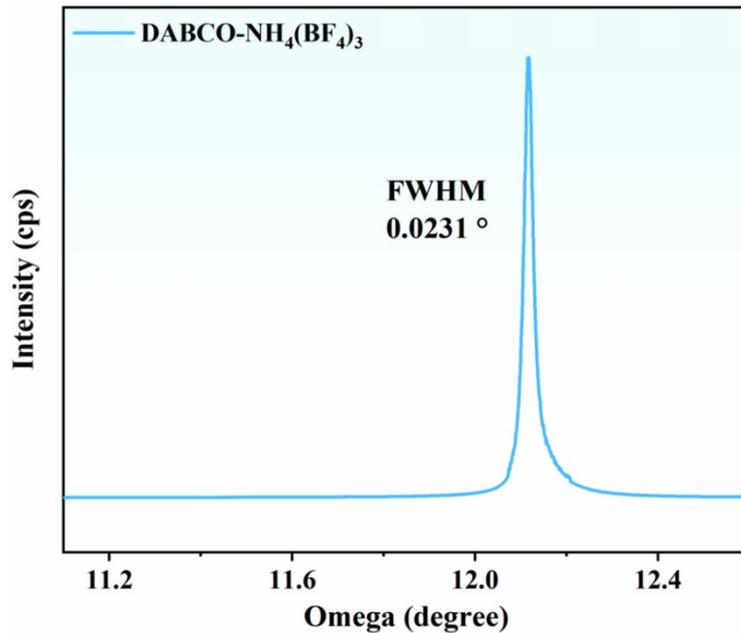


Figure S4. High-resolution XRD rocking curve of DABCO- $\text{NH}_4(\text{BF}_4)_3$ on (002) plane.

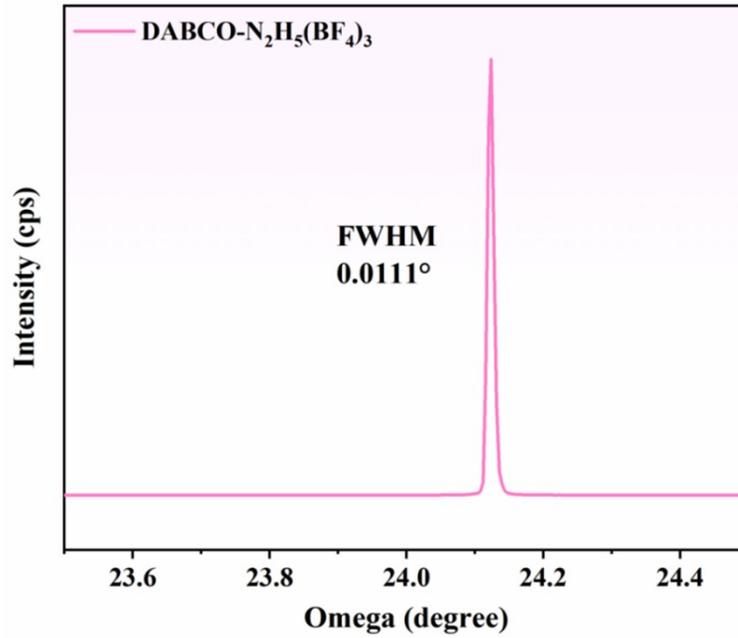


Figure S5. High-resolution XRD rocking curve of DABCO-N₂H₅(BF₄)₃ on (-405) plane.

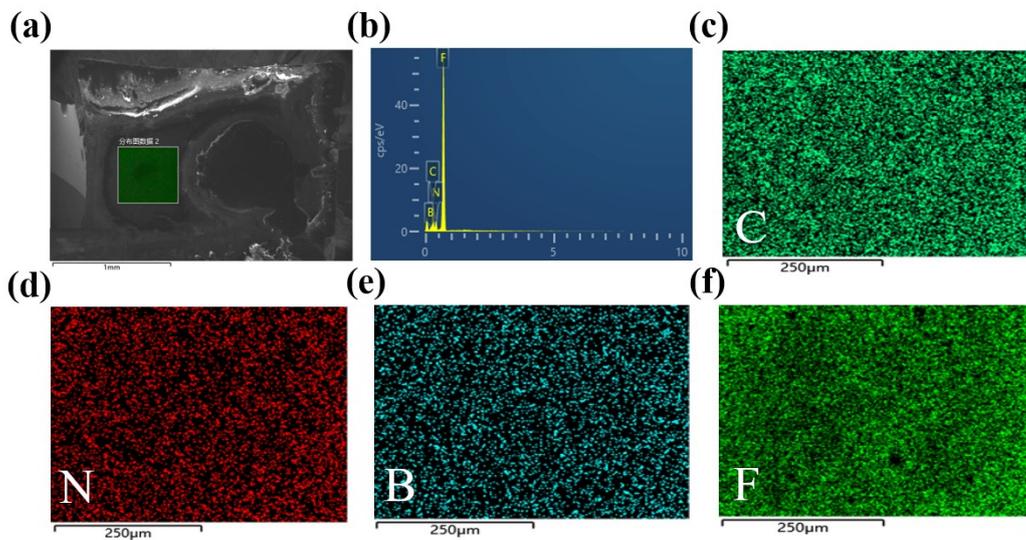


Figure S6. Element analysis of DABCO-NH₄(BF₄)₃ SC: (a) the SEM image of the EDS mapping region. (b) The corresponding EDS spectrum of DABCO-NH₄(BF₄)₃ and (c-f) the EDS mapping of C, N, B, and F, respectively.

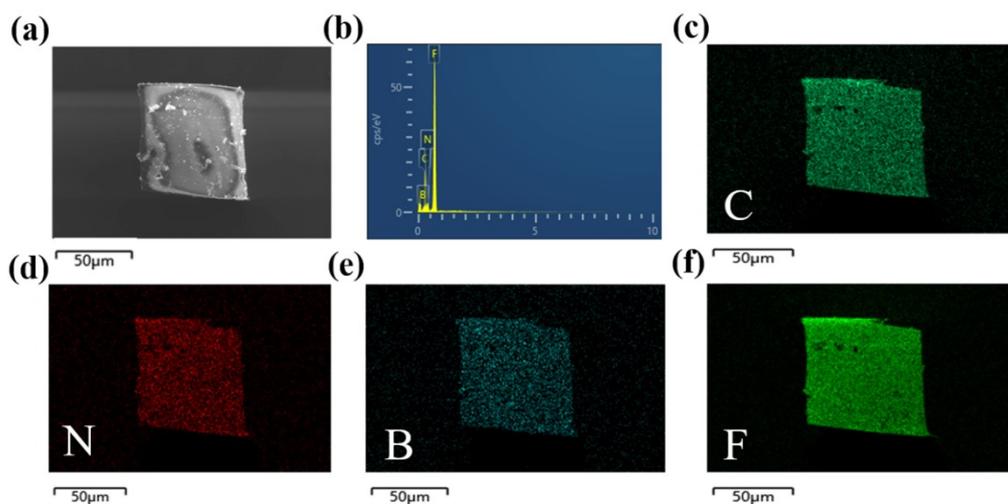


Figure S7. Element analysis of DABCO- $\text{N}_2\text{H}_5(\text{BF}_4)_3$ SC: (a) the SEM image of a selected microcrystal. (b) The corresponding EDS spectrum of DABCO- $\text{N}_2\text{H}_5(\text{BF}_4)_3$ and (c-f) the EDS mapping of C, N, B, and F, respectively.

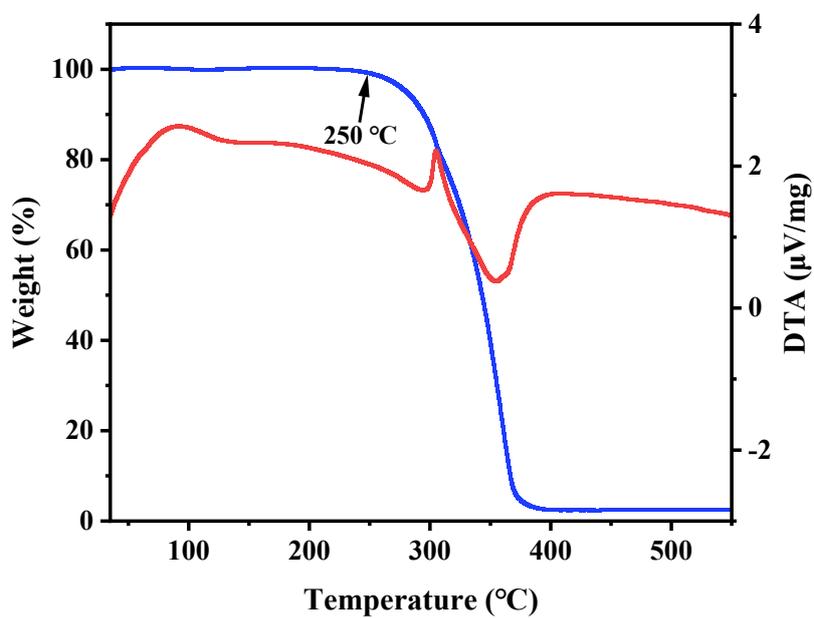


Figure S8. Thermogravimetric and DTA curves of DABCO- $\text{NH}_4(\text{BF}_4)_3$.

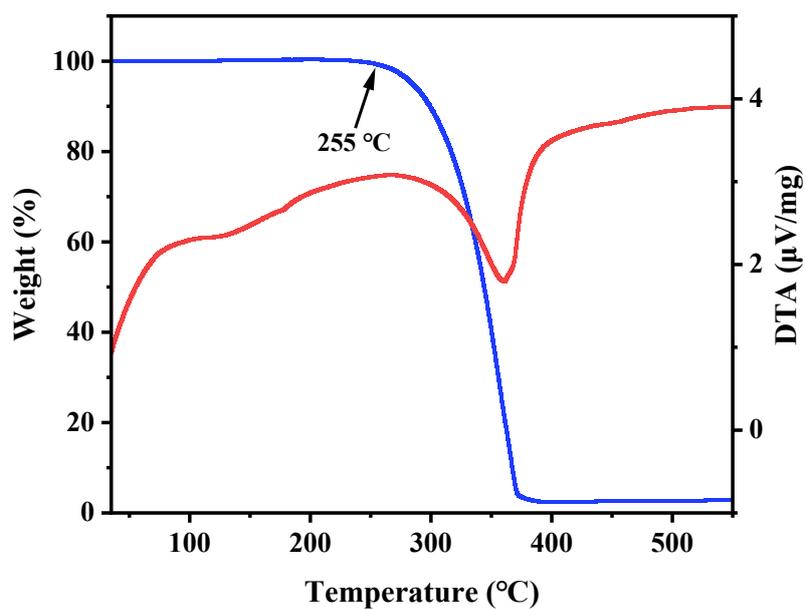


Figure S9. Thermogravimetric and DTA curves of DABCO- $\text{N}_2\text{H}_5(\text{BF}_4)_3$.

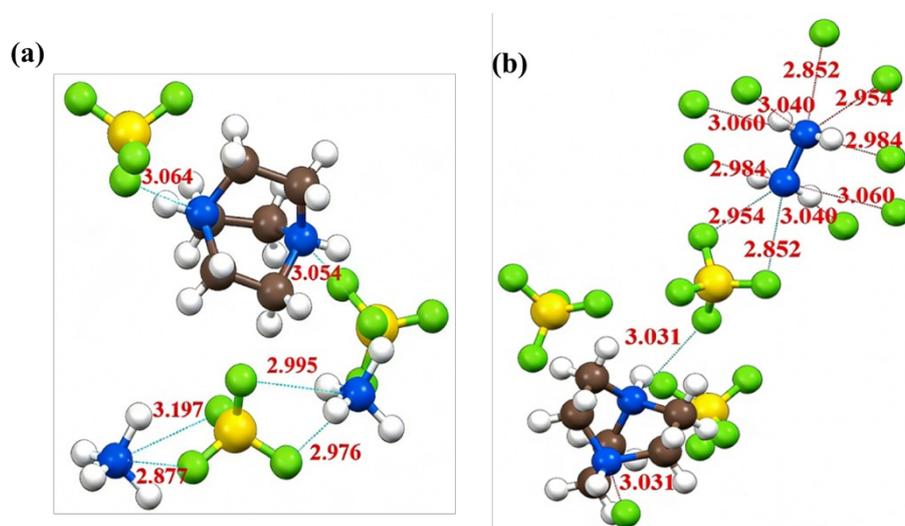


Figure S10. Schematic diagram of hydrogen bond lengths for (a) DABCO- $\text{NH}_4(\text{BF}_4)_3$ and (b) DABCO- $\text{N}_2\text{H}_5(\text{BF}_4)_3$. (Brown spheres are C, blue spheres are N, white spheres are H, yellow spheres are B, green spheres are F atoms).

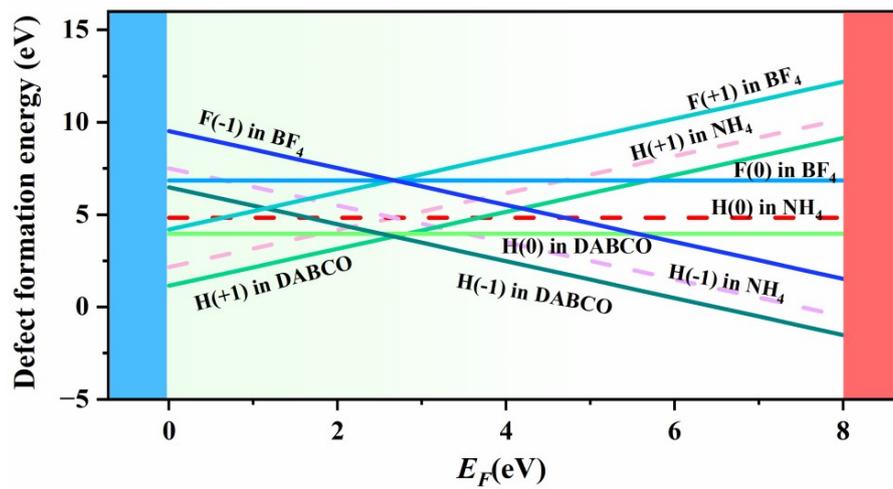


Figure S11. Defect formation energy of DABCO-NH₄(BF₄)₃.

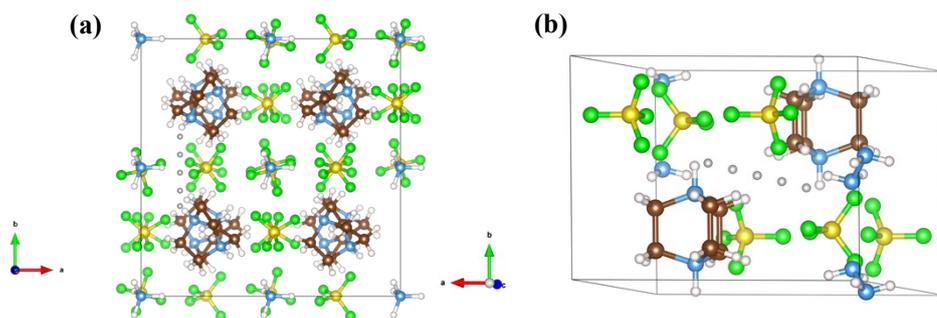


Figure S12. (a) The H-ion migration path of DABCO-NH₄(BF₄)₃; (b) The H-ion migration path of DABCO-N₂H₅(BF₄)₃.

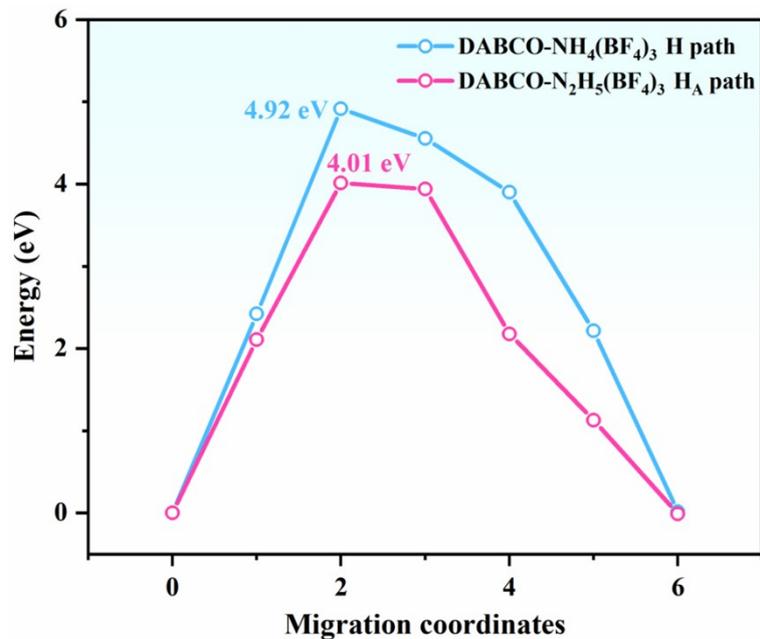


Figure S13. The calculated ionic migration energy of H ion in DABCO of the DABCO-NH₄(BF₄)₃ and H_A in N₂H₅ of the DABCO-N₂H₅(BF₄)₃. H_A represents the H atom attached to the N atom bearing a lone pair in the N₂H₅.

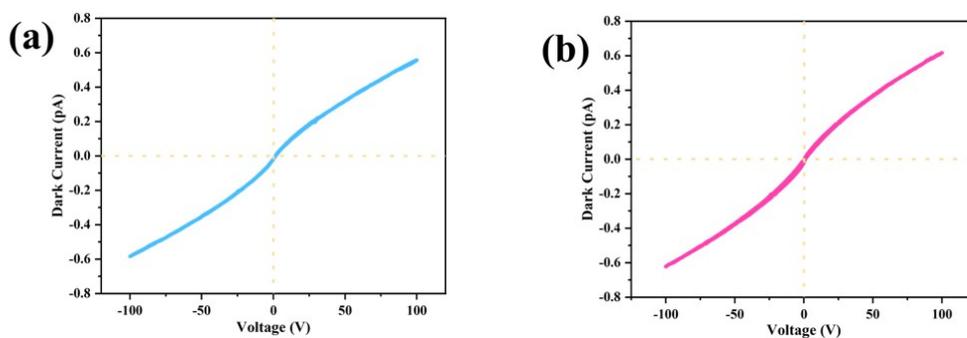


Figure S14. The forward and reverse I-V sweep curves of (a) DABCO-NH₄(BF₄)₃, (b) DABCO-N₂H₅(BF₄)₃

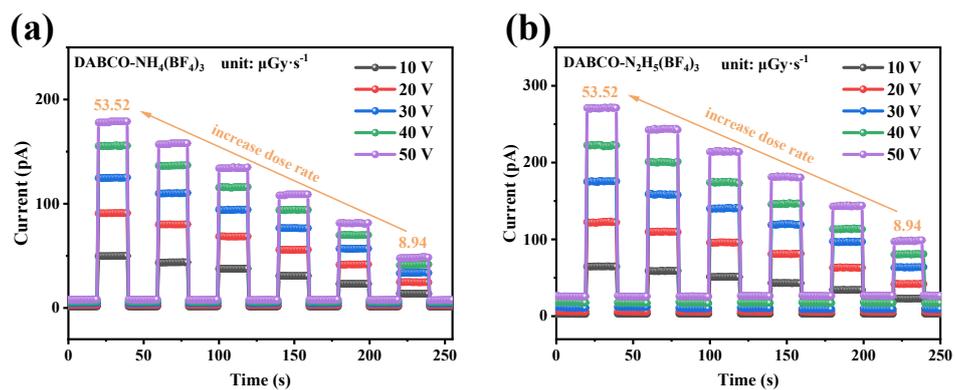


Figure S15. The current-time (I-T) measurements of (a) DABCO-NH₄(BF₄)₃ SC device and (b) DABCO-N₂H₅(BF₄)₃ SC device.

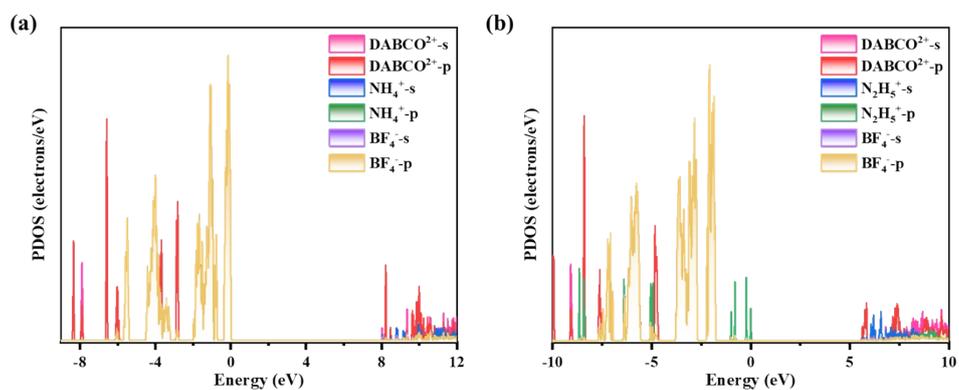


Figure S16. The calculated partial density of states (PDOS) of (a) DABCO-NH₄(BF₄)₃ and (b) DABCO-N₂H₅(BF₄)₃.

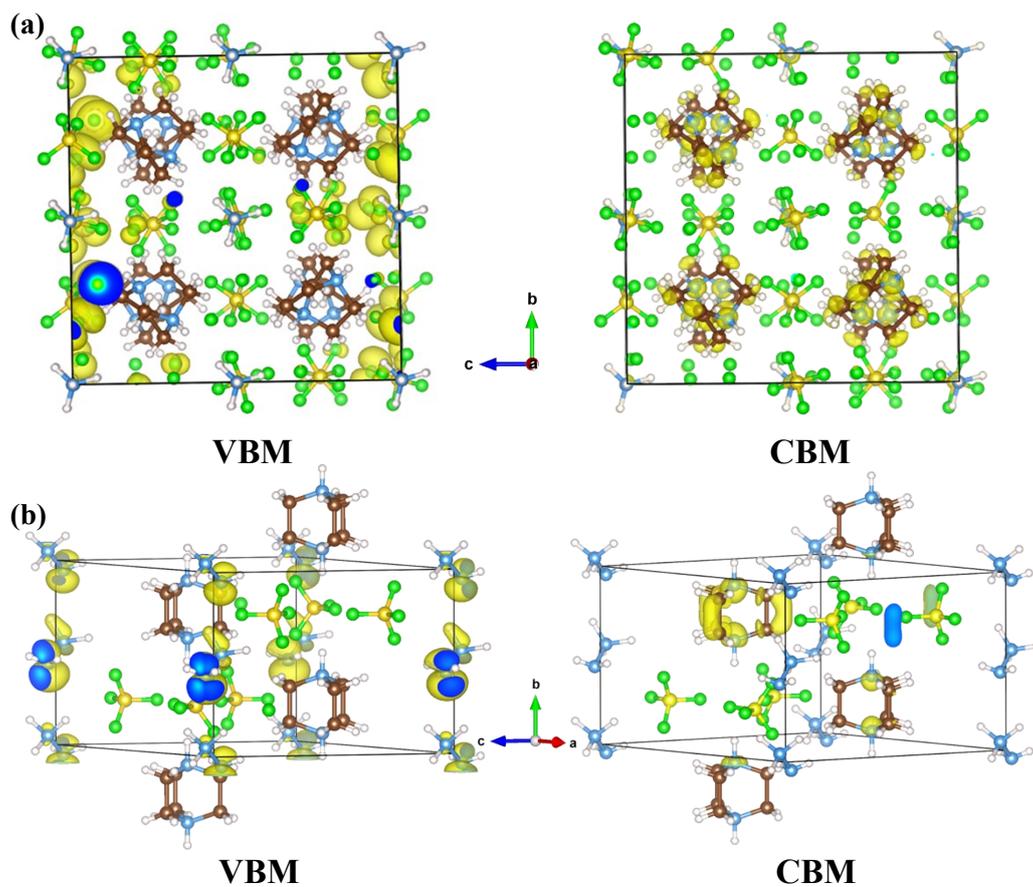


Figure S17. The diagrams of charge-density distributions for (a) DABCO-NH₄(BF₄)₃ and (b) DABCO-N₂H₅(BF₄)₃.

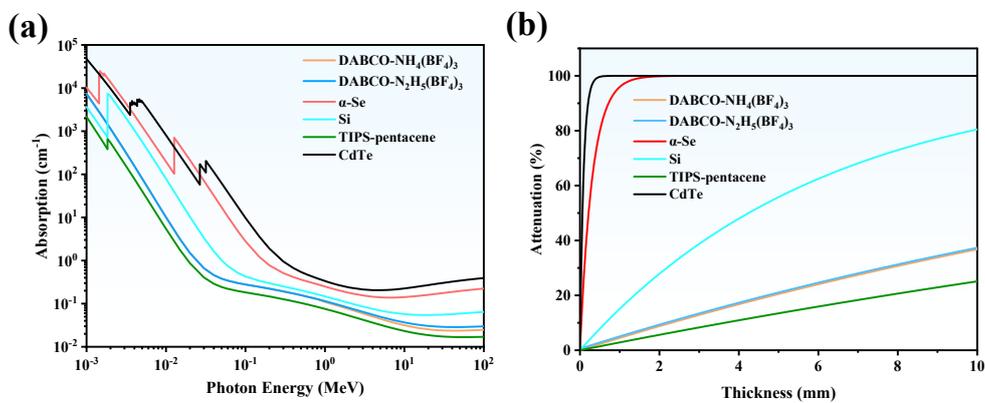


Figure S18. The absorption coefficient (a) and attenuation efficiency (b) of DABCO-NH₄(BF₄)₃, DABCO-N₂H₅(BF₄)₃, CdTe, TIPS-pentacene, α -Se and Si.

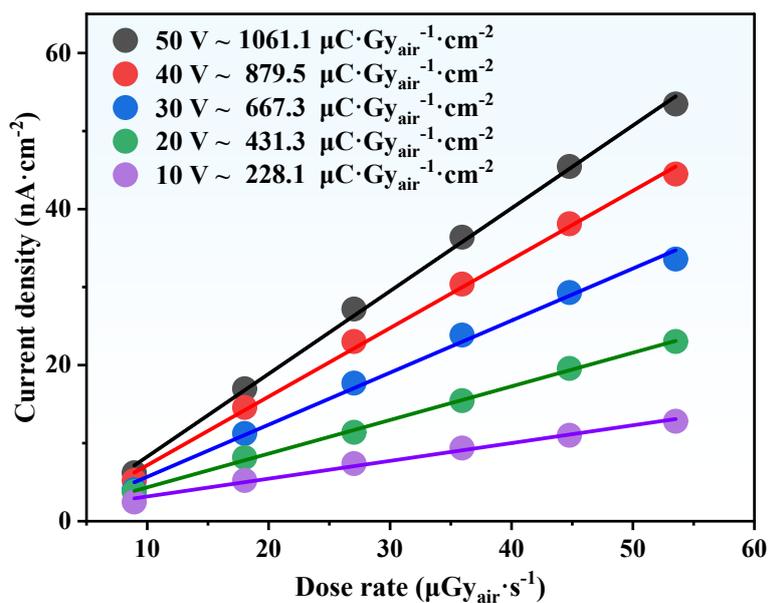


Figure S19. X-ray responses of current density with various dose rates for DABCO- $\text{N}_2\text{H}_5(\text{BF}_4)_3$ SC device along perpendicular direction.

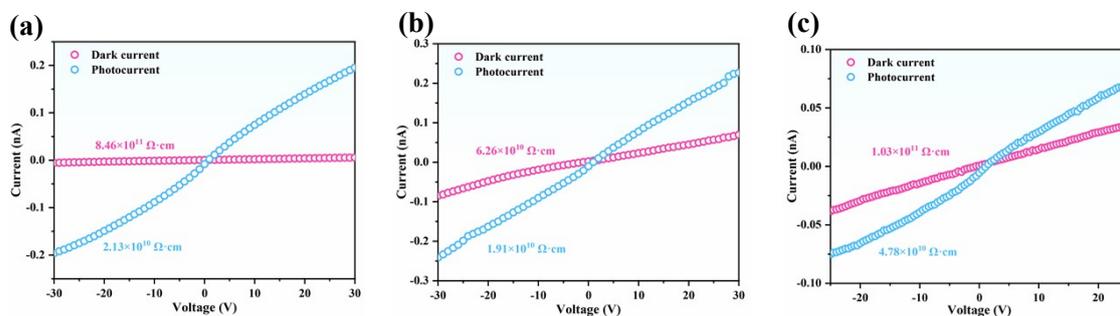


Figure S20. The resistivity measurement under X-ray on and off conditions of the (a) DABCO- $\text{NH}_4(\text{BF}_4)_3$ SC device and (b) DABCO- $\text{N}_2\text{H}_5(\text{BF}_4)_3$ SC device along the parallel and (c) perpendicular direction;

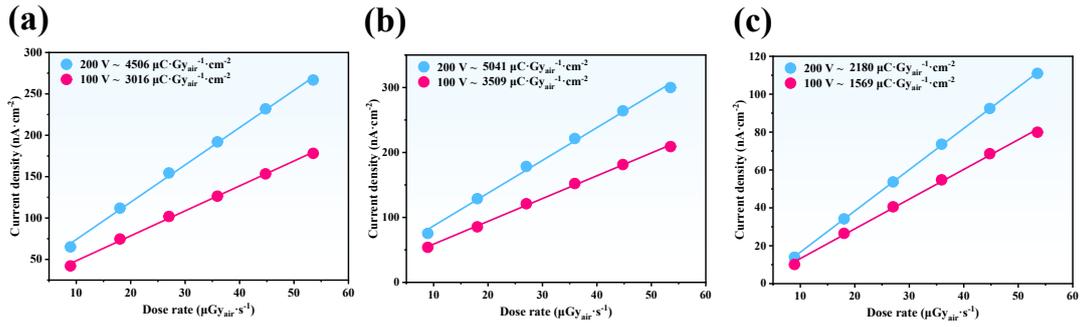


Figure S21. X-ray responses of current density with various dose rates at 100 V and 200 V for (a) DABCO-NH₄(BF₄)₃ SC device and (b) DABCO-N₂H₅(BF₄)₃ SC device along parallel direction and (c) DABCO-N₂H₅(BF₄)₃ SC device along perpendicular direction.

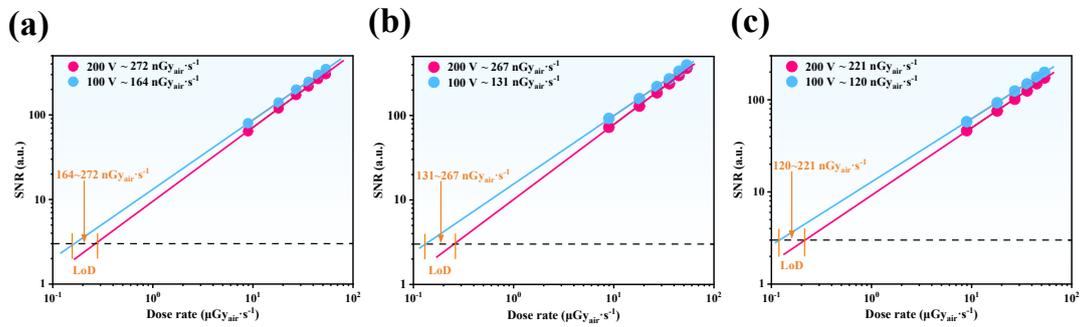


Figure S22. The signal-to-noise ratio for LoD calculations at 100 V and 200 V for (a) DABCO-NH₄(BF₄)₃ SC device and (b) DABCO-N₂H₅(BF₄)₃ SC device along parallel direction and (c) DABCO-N₂H₅(BF₄)₃ SC device along perpendicular direction.

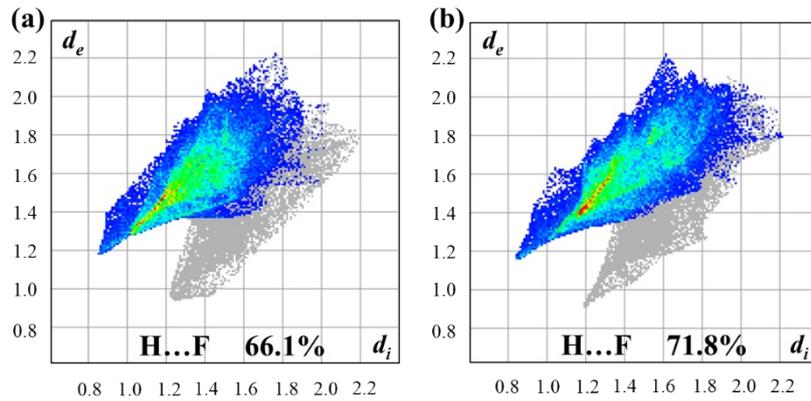


Figure S23. 2D fingerprints of H...F contacts in (a) DABCO-NH₄(BF₄)₃, (b) DABCO-N₂H₅(BF₄)₃.

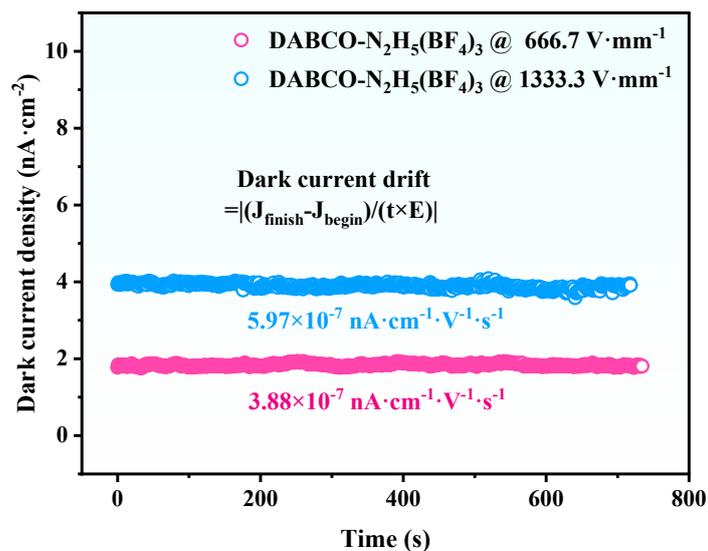


Figure S24. The dark current drift of DABCO-N₂H₅(BF₄)₃ under the electric fields of 666.6 V·mm⁻¹ and 1333.3 V·mm⁻¹.

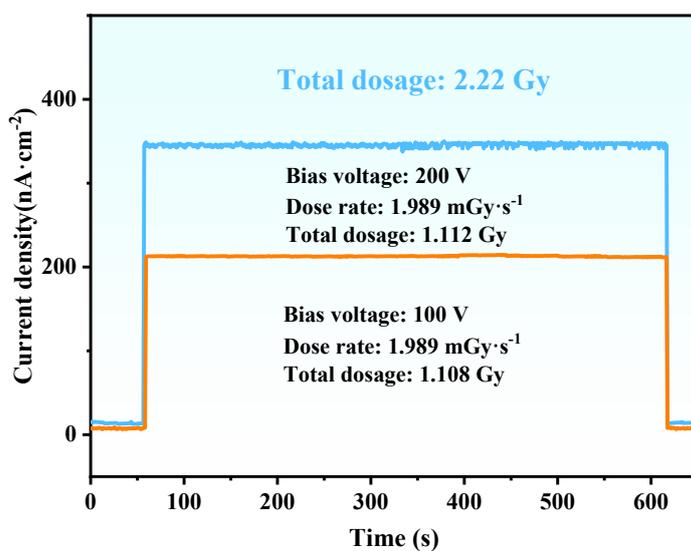


Figure S25. Current responses of the DABCO-N₂H₅(BF₄)₃ under continuous X-ray irradiation at a dose rate of 1.989 mGy·s⁻¹ with the bias voltages of 100 V and 200 V, respectively.

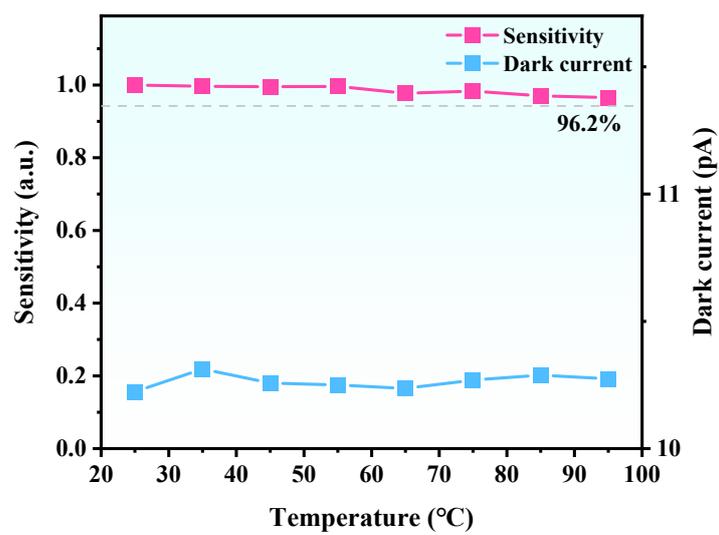


Figure S26. Stability of sensitivity and dark current of DABCO-N₂H₅(BF₄)₃ SC device under different temperatures condition.

Table S1. Ion radius in the DABCO-NH₄(BF₄)₃ and DABCO-N₂H₅(BF₄)₃.

Ions	DABCO ²⁺	NH ₄ ⁺	N ₂ H ₅ ⁺	BF ₄ ⁻
Radius (pm)	239	146	216	232

Table S2. Calculated Goldschmidt tolerance factors (*t*) of DABCO-NH₄(BF₄)₃ and DABCO-N₂H₅(BF₄)₃.

Compound	DABCO-NH ₄ (BF ₄) ₃	DABCO-N ₂ H ₅ (BF ₄) ₃
<i>t</i>	0.88	0.75

Table S3. Crystal data and structure refinement of DABCO-NH₄(BF₄)₃ and DABCO-N₂H₅(BF₄)₃.

Compound	DABCO-NH ₄ (BF ₄) ₃	DABCO-N ₂ H ₅ (BF ₄) ₃
Empirical formula	(C ₆ H ₁₄ N ₂)-NH ₄ (BF ₄) ₃	(C ₆ H ₁₄ N ₂)-N ₂ H ₅ (BF ₄) ₃
Formula weight	129.54	203.34
Temperature /K	293(2)	293(2)
Crystal system	cubic	monoclinic
Space group	<i>Pa</i> $\bar{3}$	<i>P2</i> ₁ / <i>m</i>
<i>a</i> /Å	14.2388(2)	10.3310(8)
<i>b</i> /Å	14.2388(2)	7.9328(4)
<i>c</i> /Å	14.2388(2)	10.4916(8)
α /°	90	90
β /°	90	118.426(10)
γ /°	90	90
Volume /Å ³	2886.82(12)	756.16(11)
<i>Z</i>	24	4
ρ_{calc} /gcm ⁻³	1.788	1.786
μ /mm ⁻¹	1.986	1.942
<i>F</i> (000)	1552	410
Radiation	CuK α (λ =1.54184 Å)	CuK α (λ =1.54184 Å)
2 θ range /°	10.76 to 158.26 (0.79 Å)	9.59 to 152.63(0.79 Å)
	-16 ≤ <i>h</i> ≤ 12	-12 ≤ <i>h</i> ≤ 12
Index ranges	-17 ≤ <i>k</i> ≤ 4	-9 ≤ <i>k</i> ≤ 3
	-13 ≤ <i>l</i> ≤ 17	-12 ≤ <i>l</i> ≤ 13
Reflections collected	3722	4400
	1000	1620
Independent reflections	<i>R</i> _{int} = 0.0240	<i>R</i> _{int} = 0.0318
	<i>R</i> _{sigma} = 0.0200	<i>R</i> _{sigma} = 0.0398
Data/Restraints/Parameters	1000/0/77	1620/0/133
Goodness-of-fit on <i>F</i> ²	1.101	1.074
Final <i>R</i> indexes [<i>I</i> ≥ 2σ(<i>I</i>)]	<i>R</i> ₁ = 0.0479	<i>R</i> ₁ = 0.0547
	w <i>R</i> ₂ = 0.1432	w <i>R</i> ₂ = 0.1561
Final <i>R</i> indexes [all data]	<i>R</i> ₁ = 0.0519	<i>R</i> ₁ = 0.0650
	w <i>R</i> ₂ = 0.1474	w <i>R</i> ₂ = 0.1638
Largest peak/hole/ eÅ ⁻³	0.58/-0.21	0.28/-0.22

Table S4. Bond lengths (Å) and angles (°) for DABCO-NH₄(BF₄)₃

Label	Distances (Å)	Label	Angles (°)
F1–B2	1.400(3)	C10–N8–C10#1	109.58(13)
F3–B2	1.391(3)	C10–N8–C10#2	109.58(13)
F4–B2	1.383(3)	C10#1–N8–C10#2	109.58(13)
F5–B2	1.384(3)	C10–N8–H8	109.4
N8–C10	1.494(2)	C10#1–N8–H8	109.4
N8–C10#1	1.494(2)	C10#2–N8–H8	109.4
N8–C10#2	1.494(2)	C11#1–N9–C11#2	109.57(14)
N8–H8	0.9800	C11#1–N9–C11	109.57(14)
N9–C11#1	1.493(2)	C11#2–N9–C11	109.57(14)
N9–C11#2	1.493(2)	C11#1–N9–H9	109.37(14)
N9–C11	1.493(2)	C11#2–N9–H9	109.37(14)
N9–H9	1.01(5)	C11–N9–H9	109.37(14)
C10–C11	1.523(3)	N8–C10–C11	108.15(19)
C10–H10A	0.9700	N8–C10–H10A	110.1
C10–H10B	0.9700	C11–C10–H10A	110.1
C11–H11A	0.9700	N8–C10–H10B	110.1
C11–H11B	0.9700	C11–C10–H10B	110.1
		H10A–C10–H10B	108.4
		N9–C11–C10	108.19(19)
		N9–C11–H11A	110.1
		C10–C11–H11A	110.1
		N9–C11–H11B	110.1
		C10–C11–H11B	110.1
		H11A–C11–H11B	108.4
		F4–B2–F5	110.2(2)
		F4–B2–F3	110.32(18)
		F5–B2–F3	108.97(19)
		F4–B2–F1	109.50(18)
		F5–B2–F1	109.42(17)
		F3–B2–F1	108.44(19)

Symmetry transformations used to generate equivalent atoms:

#1: 1.5-z, 1-x, 0.5+y; #2: 1-y, -0.5+z, 1.5 -x.

Table S5. Bond lengths (Å) and angles (°) for DABCO-N₂H₅(BF₄)₃

Label	Distances (Å)	Label	Angles (°)
F2–B1	1.382(5)	C14–N13–C16	109.4(2)
F3–B1	1.379(3)	C14–N13–C15	110.4(2)
F4–B1	1.384(5)	C16–N13–C15	109.9(2)
F5–B6	1.376(3)	C14–N13–H13	109.0
F8–B6	1.377(5)	C16–N13–H13	109.0
F7–B6	1.377(5)	C15–N13–H13	109.0
F10–B9	1.391(6)	N1#1–N1–H1A	101(3)
F11–B9	1.365(4)	N1#1–N1–H1B	104(3)
N13–C14	1.485(4)	H1A–N1–H1B	110(4)
N13–C16	1.491(4)	N13–C15–C15#2	108.83(14)
N13–C15	1.492(3)	N13–C15–H15A	109.9
N13–H13	0.9800	C15#2–C15–H15A	109.9
F12–B9	1.369(5)	N13–C15–H15B	109.9
N1–N1#1	1.424(5)	C15#2–C15–H15B	109.9
N1–H1A	0.86(4)	H15A–C15–H15B	108.3
N1–H1B	0.84(4)	N13–C16–C16#2	109.23(15)
C15–C15#2	1.520(6)	N13–C16–H16A	109.8
C15–H15A	0.9700	C16#2–C16–H16A	109.8
C15–H15B	0.9700	N13–C16–H16B	109.8
C16–C16#2	1.501(7)	C16#2–C16–H16B	109.8
C16–H16A	0.9700	H16A–C16–H16B	108.3
C16–H16B	0.9700	N13–C14–C14#2	109.06(15)
C14–C14#2	1.514(7)	N13–C14–H14A	109.9
C14–H14A	0.9700	C14#2–C14–H14A	109.9
C14–H14B	0.9700	N13–C14–H14B	109.9
		C14#2–C14–H14B	109.9
		H14A–C14–H14B	108.3
		F5#3–B6–F5	109.7(3)
		F5#3–B6–F7	109.3(2)
		F5–B6–F7	109.3(2)
		F5#3–B6–F8	109.4(2)
		F5–B6–F8	109.4(2)
		F7–B6–F8	109.6(4)
		F3–B1–F3#3	108.9(3)
		F3–B1–F2	109.3(2)
		F3#3–B1–F2	109.3(2)
		F3–B1–F4	109.8(2)
		F3#3–B1–F4	109.8(2)

Symmetry transformations used to generate equivalent atoms: #1: -x, -y, -z; #2: +x, 1.5-y, +z; #3: +x, 0.5-y, +z.

Table S6. Atomic coordinates ($\times 10^4$) and equivalent isotropic displacement parameters ($\text{\AA}^2 \times 10^3$) for DABCO-NH₄(BF₄)₃

Atom	<i>x</i>	<i>y</i>	<i>z</i>	<i>U</i> _{eq}
F1	0.51496(10)	0.30700(10)	0.92336(9)	0.0430(4)
F3	0.55770(10)	0.18744(10)	1.01906(11)	0.0495(5)
F4	0.40492(10)	0.20345(10)	0.97471(12)	0.0516(5)
F5	0.47055(13)	0.30685(11)	1.07663(10)	0.0553(5)
N6	0.500000	0.000000	1.000000	0.0299(9)
N7	0.500000	0.500000	1.000000	0.0298(9)
N8	0.79409(12)	0.20591(12)	0.70591(12)	0.0293(7)
H8	0.833825	0.166174	0.666173	0.035
N9	0.69307(11)	0.30693(11)	0.80693(11)	0.0285(6)
C10	0.70761(16)	0.23267(17)	0.65291(15)	0.0387(6)
H10A	0.679150	0.177349	0.625154	0.046
H10B	0.723366	0.276153	0.602892	0.046
C11	0.63944(17)	0.2786(2)	0.72137(18)	0.0469(7)
H11A	0.610737	0.333284	0.692618	0.056
H11B	0.590098	0.234744	0.738181	0.056
B2	0.48621(17)	0.25084(15)	0.99874(16)	0.0306(5)
H9	0.6520(19)	0.3480(19)	0.8480(19)	0.045(12)

U(eq) is defined as one third of the trace of the orthogonalized *U*_{ij} tensor.

Table S7. Atomic coordinates ($\times 10^4$) and equivalent isotropic displacement parameters ($\text{\AA}^2 \times 10^3$) for DABCO- $\text{N}_2\text{H}_5(\text{BF}_4)_3$.

Atom	x	y	z	U_{eq}
F2	0.2607(3)	0.250000	0.2887(3)	0.0538(6)
F3	0.1237(2)	0.1086(2)	0.3679(2)	0.0600(5)
F4	0.3263(3)	0.250000	0.5277(3)	0.0657(8)
F5	0.6552(2)	0.1083(2)	0.7711(2)	0.0696(6)
F8	0.5132(3)	0.250000	0.8434(3)	0.0681(8)
F7	0.7595(3)	0.250000	0.9817(3)	0.0721(9)
F10	0.0041(3)	0.250000	0.7730(4)	0.0714(8)
F11	0.2154(3)	0.3912(3)	0.8933(3)	0.0835(7)
N13	0.3334(2)	0.5935(3)	0.6712(2)	0.0399(5)
H13	0.333036	0.469933	0.671349	0.048
F12	0.1720(4)	0.250000	0.6922(4)	0.0930(12)
N1	0.0410(3)	0.0545(3)	0.0599(3)	0.0472(6)
H1A	0.130(5)	0.028(6)	0.080(4)	0.071
H1B	0.023(4)	0.017(6)	0.125(4)	0.071
C15	0.3883(3)	0.6542(4)	0.5711(3)	0.0467(7)
H15A	0.325354	0.612540	0.473872	0.056
H15B	0.487268	0.612538	0.602774	0.056
C16	0.1804(3)	0.6554(4)	0.6211(4)	0.0539(8)
H16A	0.143964	0.613891	0.685015	0.065
H16B	0.116217	0.613891	0.524100	0.065
C14	0.4301(4)	0.6546(4)	0.8209(3)	0.0544(8)
H14A	0.529482	0.613038	0.854934	0.065
H14B	0.394563	0.613045	0.885555	0.065
B6	0.6457(5)	0.250000	0.8418(5)	0.0381(9)
B1	0.2091(4)	0.250000	0.3884(5)	0.0365(8)
B9	0.1532(5)	0.250000	0.8129(5)	0.0426(10)

U_{eq} is defined as one third of the trace of the orthogonalized U_{ij} tensor.

Table S8. Anisotropic displacement parameters ($\text{\AA}^2 \times 10^3$) for DABCO-NH₄(BF₄)₃.The anisotropic displacement factor exponent takes the form: $-2\pi^2 [h^2 a^{*2} U_{11} + \dots + 2hka^* b^*U_{12}]$

Atom	U_{11}	U_{22}	U_{33}	U_{23}	U_{13}	U_{12}
F1	0.0481(8)	0.0417(8)	0.0392(7)	0.0079(5)	0.0030(6)	-0.0019(6)
F3	0.0470(9)	0.0448(8)	0.0568(9)	0.0088(6)	-0.0051(7)	0.0098(6)
F4	0.0413(8)	0.0524(9)	0.0610(10)	-0.0007(7)	-0.0052(7)	-0.0138(6)
F5	0.0765(12)	0.0499(9)	0.0396(8)	-0.0118(6)	0.0080(7)	-0.0005(7)
N6	0.0299(9)	0.0299(9)	0.0299(9)	-0.0035(10)	0.0035(10)	-0.0035(10)
N7	0.0298(9)	0.0298(9)	0.0298(9)	-0.0013(9)	0.0013(9)	0.0013(9)
N8	0.0293(7)	0.0293(7)	0.0293(7)	-0.0033(6)	0.0033(6)	0.0033(6)
N9	0.0285(6)	0.0285(6)	0.0285(6)	-0.0035(6)	0.0035(6)	0.0035(6)
C10	0.0424(12)	0.0426(12)	0.0310(11)	-0.0089(9)	-0.0093(9)	0.0064(9)
C11	0.0370(12)	0.0550(14)	0.0488(14)	-0.0157(11)	-0.0151(10)	0.0153(10)
B2	0.0326(11)	0.0295(11)	0.0298(11)	-0.0007(8)	0.0001(9)	-0.0007(9)

Table S9. Anisotropic displacement parameters ($\text{\AA}^2 \times 10^3$) for DABCO-N₂H₅(BF₄)₃.The anisotropic displacement factor exponent takes the form: $-2\pi^2 [h^2 a^{*2} U_{11} + \dots + 2hka^* b^*U_{12}]$

Atom	U_{11}	U_{22}	U_{33}	U_{23}	U_{13}	U_{12}
F2	0.0480(13)	0.0667(16)	0.0527(14)	0.000	0.0289(11)	0.000
F3	0.0695(12)	0.0449(10)	0.0655(11)	0.0000(8)	0.0322(10)	-0.0164(8)
F4	0.0549(15)	0.083(2)	0.0400(13)	0.000	0.0069(11)	0.000
F5	0.0857(14)	0.0450(11)	0.0835(14)	-0.0171(9)	0.0446(12)	0.0012(9)
F8	0.0477(14)	0.099(2)	0.0647(17)	0.000	0.0321(13)	0.000
F7	0.0544(16)	0.089(2)	0.0519(15)	0.000	0.0085(12)	0.000
F10	0.0597(16)	0.077(2)	0.080(2)	0.000	0.0361(15)	0.000
F11	0.1006(17)	0.0564(13)	0.0986(17)	-0.0256(12)	0.0515(14)	-0.0276(12)
N13	0.0534(13)	0.0255(10)	0.0449(12)	-0.0016(9)	0.0268(11)	-0.0004(9)
F12	0.104(3)	0.133(3)	0.0648(19)	0.000	0.0589(19)	0.000
N1	0.0462(13)	0.0555(15)	0.0353(11)	-0.0063(11)	0.0156(10)	-0.0004(11)
C15	0.0569(16)	0.0452(16)	0.0510(15)	-0.0057(13)	0.0363(13)	-0.0001(13)
C16	0.0409(14)	0.0562(18)	0.071(2)	-0.0135(16)	0.0315(14)	-0.0108(14)
C14	0.0706(19)	0.0457(17)	0.0368(14)	0.0071(12)	0.0173(13)	0.0133(15)
B6	0.039(2)	0.032(2)	0.043(2)	0.000	0.0197(18)	0.000
B1	0.036(2)	0.035(2)	0.037(2)	0.000	0.0169(17)	0.000
B9	0.055(3)	0.031(2)	0.050(2)	0.000	0.032(2)	0.000

Table S10. Band gaps and resistivity of different MFPS

Compound	Band gap	Resistivity ($\Omega \cdot \text{cm}$)	Ref
DABCO-NH ₄ (BF ₄) ₃	8.13 eV	8.46×10^{11}	This work
DABCO-N ₂ H ₅ (BF ₄) ₃ (II)	5.48 eV	6.26×10^{10}	This work
DABCO-N ₂ H ₅ (BF ₄) ₃ (I)	5.48 eV	1.03×10^{11}	This work
DABCO-N ₂ H ₅ Br ₃	5.47 eV	$2.74 \pm 1.42 \times 10^{10}$	12
DABCO-N ₂ H ₅ I ₃	4.79 eV	$1.26 \pm 0.02 \times 10^{10}$	12
MDABCO-NH ₄ I ₃	4.95 eV	1.90×10^7	13
MDABCO-NH ₄ (PF ₆) ₃	7.96 eV	7.94×10^9	14
NDABCO-NH ₄ Br ₃	3.14 eV	1.67×10^9	15
(3-AP)-NH ₄ I ₃	4.50 eV	3.63×10^9	16

Table S11. Summary on the key parameters of MFPs X-ray detectors.

Compound	Electric field / bias	Type	Sensitivity ($\mu\text{C}\cdot\text{Gy}_{\text{air}}^{-1}\cdot\text{cm}^{-2}$)	LoD ($\text{nGy}_{\text{air}}\cdot\text{s}^{-1}$)	Ref
DABCO-N ₂ H ₅ Br ₃	200 V	SC	1143	2680	12
DABCO-N ₂ H ₅ I ₃	200 V	SC	1187	2880	12
MDABCO-NH ₄ I ₃	50 V	SC	1997	>5500	13
MDABCO-NH ₄ (PF ₆) ₃	50 V	SC	2078	16.3	14
NDABCO-NH ₄ Br ₃	10 V	SC	623	970	15
(3-AP)-NH ₄ I ₃	50 V	SC	1556	1140	16
DABCO-NH ₄ Cl ₃	50 V	SC	165	>5500	17
DABCO-NH ₄ Br ₃	50 V	SC	176	4960	17
DABCO-NH ₄ I ₃	50 V	SC	567	>5500	17
MDABCO-NH ₄ (BF ₄) ₃	200 V·mm ⁻¹	SC	617	155	18
MDABCOCl-NH ₄ (BF ₄) ₃	200 V·mm ⁻¹	SC	1522	68.2	18
MDABCOBr-NH ₄ (BF ₄) ₃	200 V·mm ⁻¹	SC	2337	50.1	18
DABCO-NH ₄ (BF ₄) ₃	50 V	SC	1931	30.2	This work
DABCO-N ₂ H ₅ (BF ₄) ₃	50 V	SC	2570 (II) 1061 (I)	20.9 (II) 35.3 (I)	This work

Table S12. Ion migration energy of DABCO-NH₄(BF₄)₃ and DABCO-N₂H₅(BF₄)₃ in comparison with most reported MFPs and lead-based perovskites.

Material	Ion migration energy	Ref
DABCO-NH ₄ (BF ₄) ₃	4.01	This Work
DABCO-N ₂ H ₅ (BF ₄) ₃	4.92	This Work
(DABCO)-N ₂ H ₅ (NH ₄) ₂ Cl ₉	0.75	12
DABCO-N ₂ H ₅ Br ₃	0.99	12
DABCO-N ₂ H ₅ I ₃	1.09	12
MDABCO-NH ₄ I ₃	~0.80	13
MDABCO-NH ₄ (BF ₄) ₃	~4.10	18
(MDABCOCl)-NH ₄ (BF ₄) ₃	~4.25	18
(MDABCOBr)-NH ₄ (BF ₄) ₃	~5.10	18
MDABCO-NH ₄ (PF ₆) ₃	~6.00	14
(CHMA) ₂ PbCl ₄	0.69	19
(4-AMPD)PbCl ₄	1.00	19
(PbCl ₂) ₂ (4-AMTP) ₂ PbCl ₄	1.64	19

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